

PATENT NUMBER:

U.S. UTILITY Patent Application

RW O.I.P.E. SCANNED PD 2 O.A. AA	PATENT DATE:
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APPLICATION NO.	CONT/PRIOR	CLASS	SUBCLASS	ART UNIT	EXAMINER
09/597161	F	257	632	315 2811	Dray

APPLICANTS
 Ichiro Okabe
 Hiroki Arai

TITLE
 Method of forming a fine pattern, and method of manufacturing a semiconductor device, and a semiconductor device having a fine pattern

PTO-2040
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[illegible]

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